



Ready to use mixed resins

Ready to use mixed resins produce high purity water more conveniently. Up to the usage of water volume, they are widely used for cartridges or pressure vessels that do not require a complicated regeneration process. The primary application for TRILITE SM200, SM210 is in Wire EDM applications. It features an outstanding amount of treated water compared to other ready-to-use mixed resins in the market. TRILITE SM300 used after RO(Reverse osmosis) in Make-up systems, results in treated water quality close to that of Ultrapure water (Resistivity > 15.0MΩ-cm). UPW Grade mixed resins UPRM Series is used for the Final polisher in the UPW process (Pre-treatment → Demineralization → UPW production).

Application wise major features and treated water quality

Grade	Feature & Application	Components	Water quality	
			Inlet	Outlet
SM200	Simple production from potable water EDM(Wire-cutting)	Cation (H ⁺ 99.0%↑) Anion (OH ⁻ 90.0%↑)	Potable Water Conductivity 150μs/cm SV36	Guaranteed Resistivity >10.0 MΩ-cm (in 10min.)
				Actual Resistivity >15.0 MΩ-cm (in 10min.)
SM210	Simple production from potable water Demineralization	Cation (H ⁺ 99.0%↑) Anion (OH ⁻ 95.0%↑)	Post-RO Conductivity 10μs/cm SV36	Guaranteed Resistivity >10.0 MΩ-cm (in 10min.)
				Actual Resistivity >15.0 MΩ-cm (in 10min.)
SM300	High resistivity excellent SiO ₂ removal Post RO, EDI MB	Cation (H ⁺ 99.0%↑) Anion (OH ⁻ 95.0%↑)	UPW >17.5 MΩ-cm TOC < 2ppb SV30	Guaranteed Resistivity >15.0 MΩ-cm (in 10min.)
				Actual Resistivity >17.0 MΩ-cm (in 10min.)
UPRM100U (UPS)	Very high resistivity Electronic Grade UPW	Cation (H ⁺ 99.0%↑) Anion (OH ⁻ 95.0%↑)		Guaranteed Resistivity >17.0 MΩ-cm (in 10min.)
				Actual Resistivity >18.0 MΩ-cm (in 10min.)
UPRM200U (UPS)	Very high resistivity Low ΔTOC OLED UPW Final polisher	Cation (H ⁺ 99.9%↑) Anion (OH ⁻ 95.0%↑)		Resistivity >18.1 MΩ-cm (in 30min.) ΔTOC < 5ppb (in 120min)
UPRM300U (UPS)	Very high resistivity Very low ΔTOC Semicon. UPW Final polisher	Cation (H ⁺ 99.9%↑) Anion (OH ⁻ 97.0%↑)		Resistivity >18.2 MΩ-cm (in 30min.) ΔTOC < 1ppb (in 180min)
UPRM400U (UPS)	Very high resistivity Very low ΔTOC Low metal ion leakage Semicon. UPW Final polisher	Cation (H ⁺ 99.9%↑) Anion (OH ⁻ 97.0%↑)		Resistivity >18.2 MΩ-cm (in 30min.) ΔTOC < 1ppb (in 180min) Metal ion leakage < 0.1 ppt

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Type	Ready to use mixed resins		
	SM200	SM210	SM300
Grade	SM200	SM210	SM300
Matrix	Polystyrene+DVB		
Functional group	Mixed resin		
Shipping weight (g/ℓ)	700		
Particle size (μm)	300~1,200 (Uniformity coefficient, 1.6 ↓)		
Operating temp. (°C)	50 ↓		
Ionic form	H ⁺ (H% 99.0%↑) OH ⁻ (OH% 90.0%↑)	H ⁺ (H% 99.0%↑) OH ⁻ (OH% 95.0%↑)	H ⁺ (H% 99.0%↑) OH ⁻ (OH% 95.0%↑)
Mixed ratio (Volume)	45:55	45:55	40:60
Operating capacity (eq/ℓ)	0.4 ↑ (Feed : Conduct. 150μs/cm Potable water, SV36)	0.5 ↑ (Feed : Conduct. 150μs/cm Potable water, SV36)	0.5 ↑ (Feed : Conduct. 10μs/cm RO outlet, SV36)
Outlet condition (Resistivity)	Resistivity > 10.0 MΩ-cm (Feed : Potable water)	Resistivity > 10.0 MΩ-cm (Feed : Potable water)	Resistivity > 15.0 MΩ-cm (Feed : RO outlet)

※ The data for Shipping weight and Operating capacity is for reference.